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Ausschnitt et al.

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(54) **DIFFERENTIAL DOSE AND FOCUS MONITOR**

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(71) Applicant: **GLOBALFOUNDRIES INC.**, Grand Cayman (KY)

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(72) Inventors: **Christopher P. Ausschnitt**, Naples, FL (US); **Timothy A. Brunner**, Ridgefield, CT (US)

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(73) Assignee: **GLOBALFOUNDRIES INC.**, Grand Cayman (KY)

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(21) Appl. No.: **14/033,593**

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Primary Examiner — Colin Kreutzer

(74) *Attorney, Agent, or Firm* — Scully Scott Murphy and Presser

(51) **Int. Cl.**

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(57) **ABSTRACT**

A dose and focus monitor structure includes at least one complementary set of unit dose monitors and at least one complementary set of unit focus monitors. Each complementary set of unit dose monitors generate edges on a photoresist layer such that the edges move in opposite directions as a function of a dose offset. Each complementary set of unit focus monitors generates edges on the photoresist layer such that the edges move in opposite directions as a function of a focus offset. The dose and focus monitor structure generates self-compensating differential measurements of the dose offset and the focus offset such that the dose offset measurement and the focus offset measurement are independent of each other.

(52) **U.S. Cl.**

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(58) **Field of Classification Search**

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See application file for complete search history.

18 Claims, 15 Drawing Sheets

